



2-25-05

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JMW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Steve Biellak, et al.
Title: System and Methods for a Wafer Inspection System Using Multiple Angles and Multiple Wavelength Illumination
Application No.: 09/891,693 Filing Date: June 26, 2001
Examiner: Hoa Q. Pham Group Art Unit: 2877
Docket No.: TNCR.179US0 (M-10693 US) Conf. No.: 1752

Mail Stop RCE
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

REQUEST FOR CONTINUED EXAMINATION (RCE)

Dear Sir:

This is a Request for Continued Examination (RCE) under 37 C.F.R. § 1.114 of the above-identified application.

Please consider the Response to Office Action and Terminal Disclaimer which are being filed herewith. The RCE fee required under 37 C.F.R. § 1.17(e) is authorized in an accompanying transmittal letter.

Please contact the undersigned attorney with any questions concerning this request or the above-identified patent application.

EXPRESS MAIL NO.:

EV321704785US

February 22, 2005

Respectfully submitted,

James S. Jusue
Reg. No. 29,545

2/22/05

Date